

**Abstract**

5 A wet etching apparatus and method to shorten processing time and  
to eliminate formation of unintended mask pattern are described. In the  
conventional art, after a mask pattern is formed, alien substances such as  
water mist or stain are left on the substrate. The alien substances act as an  
etching block in the wet etching process. This generates an unintended  
mask pattern. The present invention uses ultraviolet light to remove the  
alien substances prior to the etching process. When the alien substances  
are removed, the intended mask pattern is generated after the etching  
10 process. The wet etching device according to the present invention includes  
an ultraviolet cleaner and a conveyor to convey substrates to and from the  
ultraviolet cleaner. Spaces for the ultraviolet cleaner and the conveyor are  
created in the wet etching apparatus by reducing space for cassettes and  
reducing space required by the loader. As a result, alien substances can be  
removed without the need for separate sets of equipment, which reduces  
processing time, simplifies the process, and increases both productivity and  
reliability.